

Docket Number: 081468-0281487

Client Reference: P-0198.020-US



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

JOHANNES J M BASELMANS, et al.

Group Art Unit: 1756

Application No.: 09/905,198

Examiner: Mohamedulla

Filed: July 16, 2001

Confirmation No.: 3046

For: ASSIST FEATURES FOR USE IN LITHOGRAPHIC PROJECTION

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed more than three months after the U.S. filing date AND after the mailing date of the first Office Action on the merits, but before the mailing date of a Final Rejection or Notice of Allowance.

Please charge Deposit Account 033975 in the amount of \$180.00 in payment of the fee under 37 CFR 1.17(p). Please credit or debit Deposit Account 033975 as needed to ensure consideration of the disclosed information. A duplicate copy of this paper is attached.

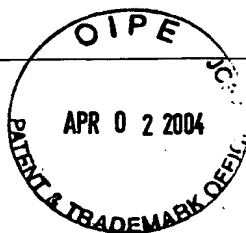
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Respectfully Submitted,

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**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: BASELMANS et al.

Appln. No.: 09/905,198

Filing Date: July 16, 2001

Date: April 2, 2004

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Examiner: Mohamedulla

Group Art Unit: 3046

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

AR	Peter D. Buck et al., "Phase Shift Mask Applications," Proceedings of SPIE – The International Society for Optical Engineering, Optical/Laser Microlithography IV, 6-8 March 1991, Coversheet + 9 pages.				
BR	Tsuneo Terasawa et al., "Improved resolution of an i-line stepper using a phase-shifting mask," J. Vac. Sci. Technol B., Vol. 8, No. 6 Nov/Dec 1990, pp. 1300-1308.				
CR	Yong Liu et al., "Computer Aided Phase Shift Mask Design with Reduced Complexity," Department of Electrical Engineering and Computer Sciences, University of California at Berkeley, CA 94720, SPIE Vol. 1927 Optical/Laser Microlithography VI (1993) pp. 477-493.				
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Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.